

Electronic Acknowledgement Receipt

EFS ID:	1184484
Application Number:	10567729
Confirmation Number:	7682
Title of Invention:	Silicon carbide epitaxial wafer, method for producing such wafer, and semiconductor device formed on such wafer
First Named Inventor:	Kazutoshi Kojima
Customer Number:	270
Filer:	William Bak
Filer Authorized By:	
Attorney Docket Number:	OGOSH46USA
Receipt Date:	05-SEP-2006
Filing Date:	01-FEB-2006
Time Stamp:	09:35:23
Application Type:	U.S. National Stage under 35 USC 371
International Application Number:	

Payment information:

Submitted with Payment	no
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File Listing:

Document Number	Document Description	File Name	File Size(Bytes)	Multi Part	Pages
1	Information Disclosure Statement (IDS) Filed	US_IDS_Form__SB_08a.pdf	1587281	no	4

Warnings:**Information:**

2	Foreign Reference	ForeignRef.pdf	640140	no	7
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Warnings:**Information:**

Total Files Size (in bytes):	2227421
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New Applications Under 35 U.S.C. 111

If a new application is being filed and the application includes the necessary components for a filing date (see 37 CFR 1.53(b)-(d) and MPEP 506), a Filing Receipt (37 CFR 1.54) will be issued in due course and the date shown on this Acknowledgement Receipt will establish the filing date of the application.

National Stage of an International Application under 35 U.S.C. 371

If a timely submission to enter the national stage of an international application is compliant with the conditions of 35 U.S.C. 371 and other applicable requirements a Form PCT/DO/EO/903 indicating acceptance of the application as a national stage submission under 35 U.S.C. 371 will be issued in addition to the Filing Receipt, in due course.